Application Serial No
Filing Date August 31, 2000
Inventor Keiji Jono et al.
Assignee KMT Semiconductor, LTD
Group Art Unit
Examiner Quang D. Vu
Attorney's Docket No KM1-001
Title: Methods of Forming an Isolation Trench in a Semiconductor, Methods of
Forming an Isolation Trench in a Surface of a Silicon Wafer, Methods of
Forming an Isolation Trench-Isolated Transistor, Trench-Isolated Transistor,
Trench Isolation Structures Formed in a Semiconductor, Memory Cells and
DRAMS

## SUPPLEMENTAL INFORMATION DISCLOSURE STATEMENT

References - See Attached Form PTO-1449

The Examiner's attention is directed to the references which are listed on the attached Form PTO-1449, copies of which are attached. No admission is made regarding whether all the submitted references are prior art.

Citation of the referenced art is respectfully requested.

Respectfully submitted,

Dated:  $3 - (0 - 0)^3$ 

D. Brent Kenady

Reg. No. 40,045

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FEB 13 2004
TECHNOLOGY CENTER 2800

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	АВ	6,171,924 B1	01/09/2001	Wang et al.							
	AC	6,154,417	11/28/2000	Kim							
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## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE.

Filing Date August 31, 2000
Inventor Keiji Jono et al.
Assignee KMT Semiconductor, LTD and Micron Technology, Inc.
Group Art Unit 2811
Examiner Quang D. Vu
Attorney's Docket No. KM1-001
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Respectfully submitted,

TECHNOLOGY CENTER 2800

Dated: 2-2-04

By:

D. Brent Kenady Reg. No. 40,045

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*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate		
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